

## Workshop Selection Codes

EMBO Workshop Advanced Light Microscopy - 10th International ELMI Meeting  
18 - 21 May 2010, EMBL Heidelberg, Germany

<b>Wed 19 May</b>	AHF analysentechnik AG & Rapp Optoelectronic GmbH	Andor Technology	Applied Precision Inc.	Bitplane AG	Carl Zeiss MicroImaging GmbH	CYTOO Cell Architects	GE Healthcare	Intelligent Imaging Innovations	Lambert Instruments	LaVision BioTec GmbH	Leica Microsystems	Leica Microsystems	Nikon Instruments Europe BV	Olympus Europa Holding GmbH	Olympus Europa Holding GmbH	Olympus Europa Holding GmbH	PerkinElmer LAS GmbH	Scientific Volume Imaging
14.30 – 16.00	AHF W1	AND W1	AP W1	BIT W1	CZM W1	CYT W1	GE W1	INT W1	LAM W1	LAV W1	LEI W1	SMD W1	NIK W1	OTI W1	OFR W1	MPE W1	PER W1	SVI W1
16.00 – 17.30	AHF W2	AND W2	AP W2	BIT W2	CZM W2	CYT W2	GE W2	INT W2	LAM W2	LAV W2	LEI W2	SMD W2	NIK W2	OTI W2	OFR W2	MPE W2		SVI W2

<b>Thu 20 May</b>	AHF analysentechnik AG & Rapp Optoelectronic GmbH	Andor Technology	Applied Precision Inc.	Bitplane AG	Carl Zeiss MicroImaging GmbH	CYTOO Cell Architects	GE Healthcare	Intelligent Imaging Innovations	Lambert Instruments	LaVision BioTec GmbH	Leica Microsystems	Leica Microsystems	Nikon Instruments Europe BV	Olympus Europa Holding GmbH	Olympus Europa Holding GmbH	Olympus Europa Holding GmbH	PerkinElmer LAS GmbH	Scientific Volume Imaging
14.30 – 16.00	AHF T1	AND T1	AP T1	BIT T1	CZM T1	CYT T1	GE T1	INT T1	LAM T1	LAV T1	LEI T1	SMD T1	NIK T1	OTI T1	OFR T1	MPE T1	PER T1	SVI T1
16.00 – 17.30	AHF T2	AND T2	AP T2	BIT T2	CZM T2	CYT T2	GE T2	INT T2	LAM T2	LAV T2	LEI T2	SMD T2	NIK T2	OTI T2	OFR T2	MPE T2		SVI T2